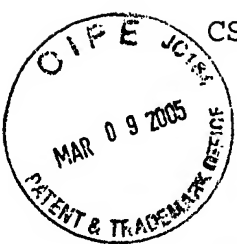


IFW



CS-03-021

March 4, 2005

To: Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Attn: Art Unit 2822 - Maria F. Guerrero

From: George O. Saile, Reg. No. 19,572

28 Davis Avenue

Poughkeepsie, N. Y., 12603

Subject: | Serial No.: 10/688,047 10/17/03 |

Chung Foong Tan et al.

END OF RANGE (EOR) SECONDARY DEFECT
ENGINEERING USING SUBSTITUTIONAL
CARBON DOPING

|_ Art Group: 2822 Maria F. Guerrero_|

RESPONSE TO RESTRICTION REQUIREMENT

This is in response to the Restriction or Election
Requirement in the Office Action dated 02/25/05. In that
Office Action, restriction was required to one of two stated

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on March 7, 2005.

Stephen B. Ackerman, Reg.# 37761

Signature/Date SB 3/7/05

Inventions under 35 U.S.C. 121. The Inventions stated are Group I - Claims 1-20 to a process, classified in Class 438, subclass 481 and Group II - Claims 21-25 to semiconductor devices, classified in Class 257, subclass 336. It is believed, and will be assumed for purposes of election, that the Examiner intended to include Claims 1-19 in Group I, and include Claim 20 in Group II, as this is a product claim.

Applicant provisionally elects to be examined the Invention described by the Examiner as Group I - Claims 1-19 drawn to a process classified in Class 438, subclass 481. This election is made with traverse of the requirement under 37 C.F.R.1.143 for the reasons given in the following paragraphs.

The Examiner is respectfully requested to reconsider the Requirement for Restriction given in the Office Action. The Examiner gives the reason for the distinctness of the two inventions as (1) that the process as claimed can be used to make other and materially different products or (2) that the product as claimed can be made by another and materially different process (MPEP 806.05(f)). However, upon reading the product Claims against the process Claims one can readily see that the product Claims are directed to "an integrated circuit device" and the process Claims are directed to "a method of preparing a wafer for integrated circuit fabrication", it is necessary to obtain claims in both the product and method claim

language. The method Claims necessarily use the product and vice versa. The field of search must necessarily cover both the method class/subclass 438/481 and products class 257/336 in addition to other related Classes and subclasses to provide a complete and adequate search. The fields of search for the Group I and Group II inventions are clearly and necessarily co-extensive. The Examiner's suggestion that "In the instant case the product as claimed can be made by another and materially different process. For example, growing an intrinsic silicon layer and implanting carbon can form the carbon-doped layer", is very speculative and really has nothing to do with the Claims as presented in this Patent Application. Further, it is respectfully suggested that these reasons are insufficient to place the additional cost of a second Patent Application upon the Applicants. Therefore, it is respectfully requested that the Examiner withdraw this restriction requirement for these reasons.

Withdrawal of the Restriction Requirement and the Allowance of the present Patent Application is requested.

Sincerely,


Stephen B. Ackerman, Reg.# 37761